MATERIALS SCIENCE X-RAY DIFFRACTION ANALYSIS LABORATORY
Philips X’Pert High Resolution Materials Research Diffractometer

MATERIALS STRUCTURES

- Semiconductor Epitaxial Layers in III-V Compounds either Perfect or Lattice Mismatched
- Highly Textured Films such as II-VI Semiconductors or High Temperature Superconductors
- Bulk Polycrystalline Materials with Texture or Stress
- X-Ray Diffraction Topography
- Non-Ambient Temperature and Environmental Chamber
- Powder Diffraction
- Amorphous and Polycrystalline Thin-film Layers

HARDWARE

- Omega--Two-theta, High Resolution Goniometers
- Direct Optical Positioning Sensing Goniometers
- Rugged Eulerian Cradle Design
- PREFIX Optical Modules
- Computer Control
- Bartels Asymmetrical Germanium Monochromator

SOFTWARE

- Automated Powder Diffraction, APD
- Rietveld Structure Analysis
- Stress Analysis, $\Psi$ and $\Omega$ Stress Methods
- High Resolution Dynamical Diffraction Simulations
- Texture, Pole Figures and Preferred Orientation
- Reflectivity Simulations at X-Ray Wavelengths

Prof. S. J. Burns, Materials Science Program, X-Ray Analysis Laboratory, Mechanical Engineering Department, University of Rochester, Rochester, NY 14627-0133 Phone (716)-275-4082